

WCAM Furnace & Oven Process Information

<u>Furnace /Oven</u>	<u>Purpose/Description</u>	<u>Temperature Range</u>	<u>Idle Temperature</u>	<u>Vacuum?</u>	<u>Material Restrictions</u>	<u>Process Gases Available</u>	<u>Furnace pre-clean required?</u>
Tystar Oxidation	Torch Si thermal oxidation	750-1050C	750C	No	No metals, see list	N2, H2, O2	Yes
MRL1	High temp anneal	750-1050C	750C	No	See list	N2, 5% H2 in N2	No
MRL2	Steam & dry Si thermal oxidation	750-1050C	750C	No	No metals, see list	N2, O2, Steam	Yes
MRL3	Steam & dry semiconductor oxidation	380-500C	380C	No	See list	N2, O2, Steam	No
MRL4	Low temp anneal	380-500C	380C	No	See list	N2, 5% H2 in N2	No
Teach Oxidation	Silicon thermal oxidation	750-1050C	750C	No	No metals, see list	N2, O2, Steam	Yes
Teach Anneal	Metal anneal	750-1050C	750C	No	See list	N2, 5% H2 in N2	No
Blue Oven	Oven for polymer processing	21-425C	21C	No	See list	N2	No
Cooke Anneal	Polyimide curing	21-400C	21C	Yes	See list	N2	No
Yes Vacuum Oven	Sample mounting	21-150C	21C	Yes	See list	None	No